

# Numerical simulation of terahertz carrier dynamics in monolayer MoS<sub>2</sub>

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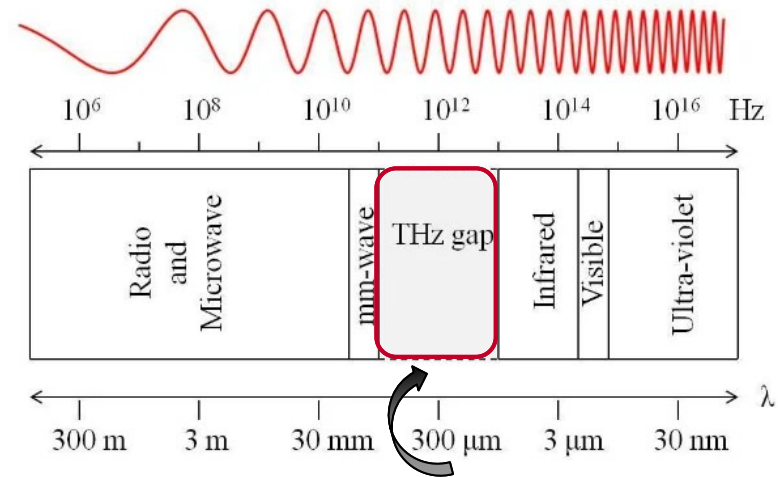


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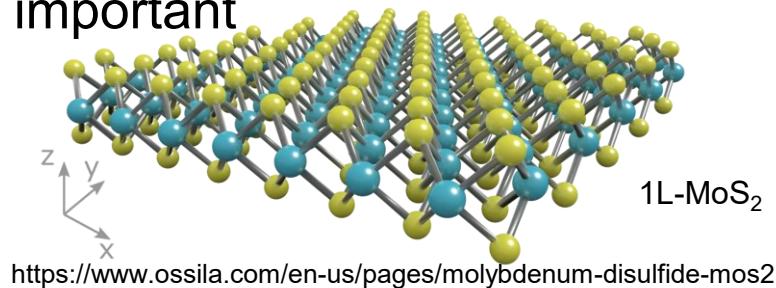
# Motivation

Terahertz (THz) excitation captures the interplay between field and carrier

- Quasi-electrostatic solvers assume  $\omega T \ll 1$ , which becomes invalid
- Needs full electrodynamic solver
- Screening plays an important role in 2D



Most 2D semiconductors have THz scattering rate

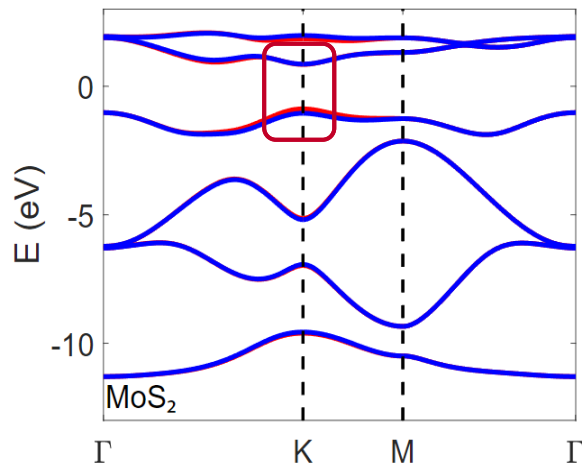
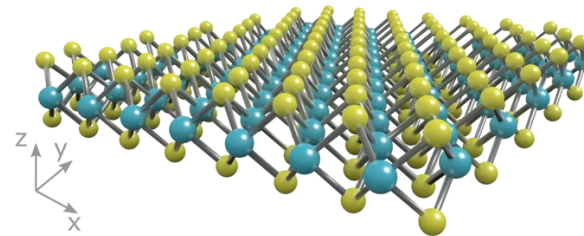


Numerical characterization of THz conductivity in 2D materials is limited

# Our work

We present a multiphysics numerical tool for THz conductivity

Monolayer MoS<sub>2</sub> is direct band, has bandgap  $\sim 1.8$  eV  $\rightarrow$  no interband (optical) transitions

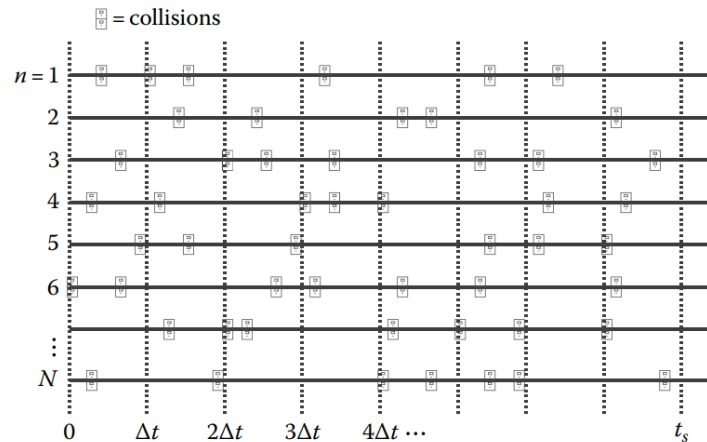
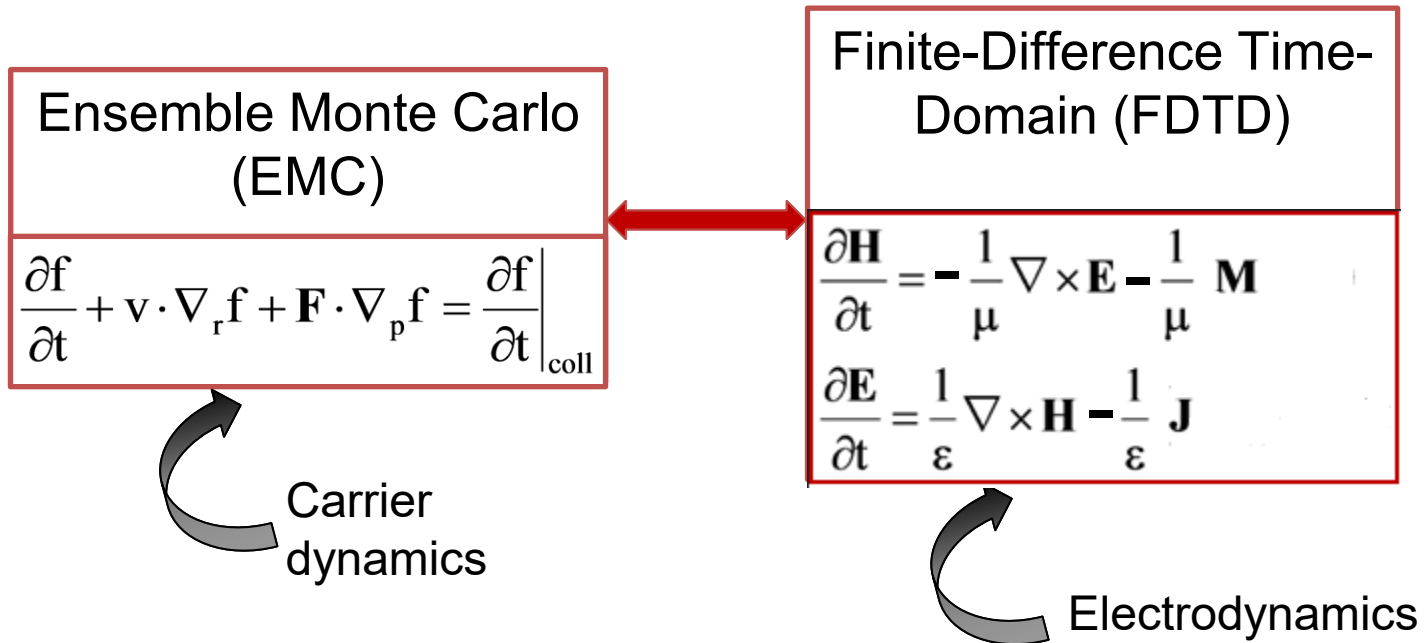


Band structure via 11-orbital basis tight binding method.

K-Q band separation  **$\sim 200$  meV**

CB K-valley  $m^* = 0.51m_0$

# Computational scheme



1. K. J. Willis, S. C. Hagness, and I. Knezevic, *Journal of Applied Physics*, vol. 110, no. 6, p. 063714, 2011.
2. N. Sule, K. J. Willis, S. C. Hagness, and I. Knezevic, *J Comput Electron* 12:563–571, 2013.

# Computational scheme

EMC:

- Employs semiclassical scattering rates

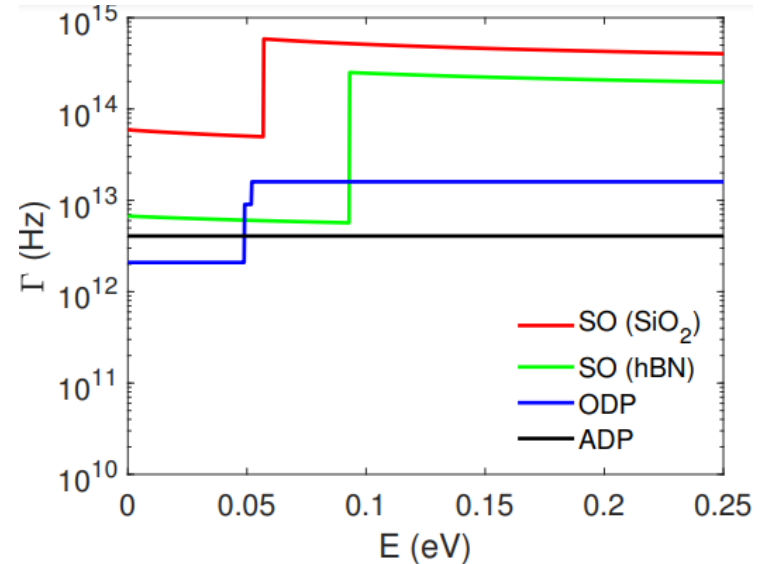
Scattering mechanisms:

- Acoustic phonon
- Optical phonon
- Surface optical (SO) phonon
- Ionized impurities

Real space distribution

$$\Gamma_{\text{ac}}(k) = \frac{D_{\text{ac}}^2 k_B T m^*}{\hbar^3 \rho_s v_s^2}$$

$$\Gamma_{\text{op}}(k) = \frac{D_{\text{op}}^2 g_d m^*}{2\hbar^2 \rho_s \omega_{\text{op}}} [N_q + (N_q + 1)\Theta(E - \hbar\omega_{\text{op}})]$$

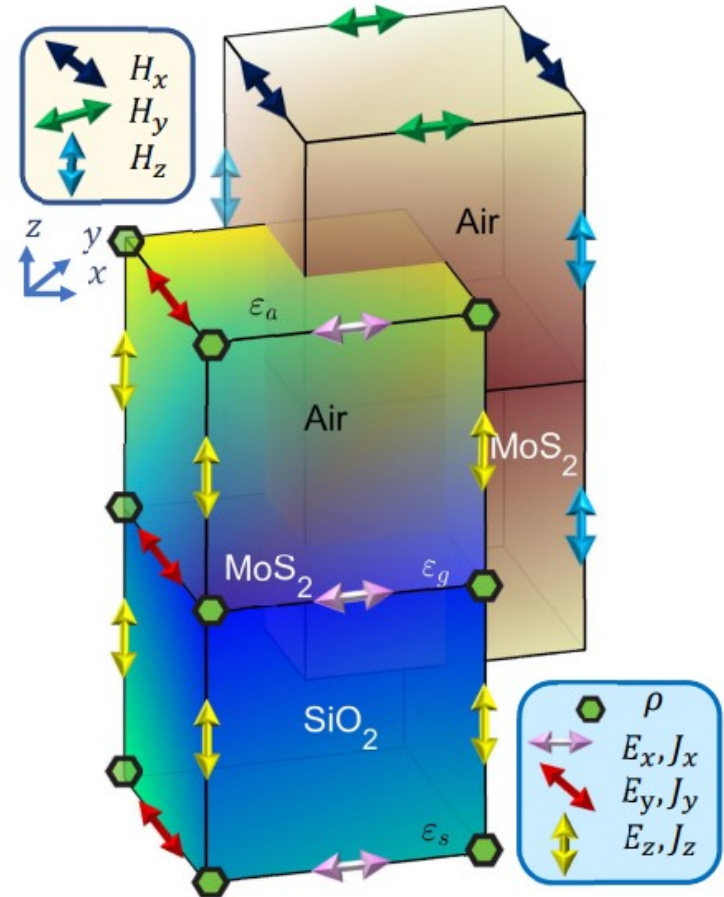
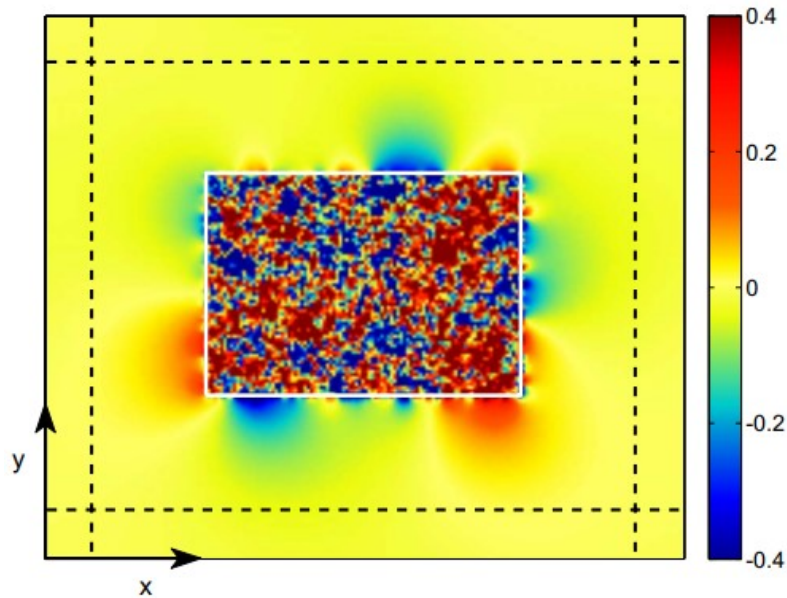


$$\Gamma_{\text{so}}(k) = \frac{32\pi^3 e^2 F_v^2 m^* S}{\hbar^3 a^2} \left( N_q + \frac{1}{2} \pm \frac{1}{2} \right) \times \int_{-\pi}^{\pi} \frac{1}{q} \frac{\sinh\left(\frac{aq}{2}\right)}{(4\pi^2 q + a^2 q^3)^2} d\theta$$

# Computational scheme

FDTD:

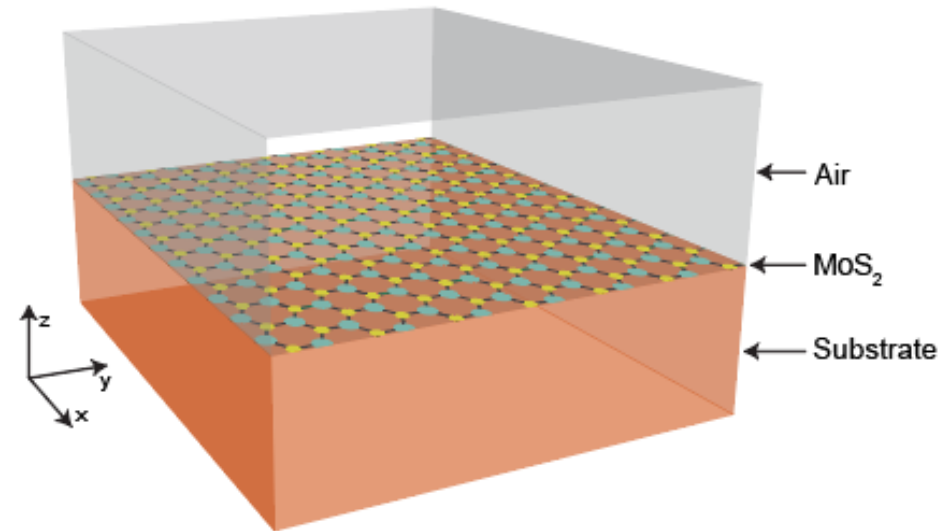
- Accurate high-frequency analyses
- Yee grid implementation
- Convolutional perfectly matched layer (CPML)
- Total-field scattered-field (TFSF) source<sup>1</sup>



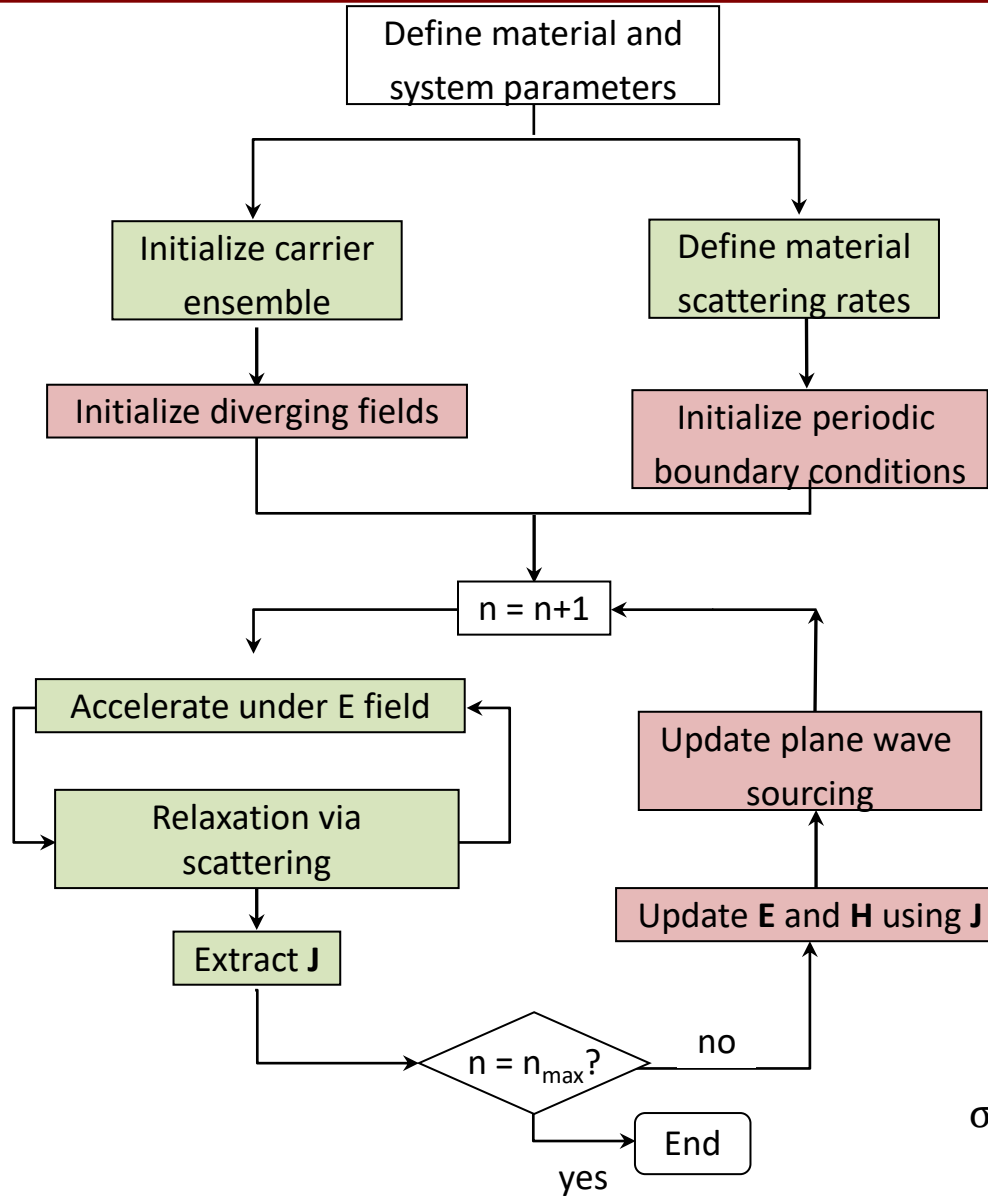
1. K. J. Willis, S. C. Hagness, and I. Knezevic, Journal of Applied Physics, vol. 110, no. 6, p. 063714, 2011

# Simulation domain

- Periodic boundary condition in  $xz$  and  $yz$  planes
- Pauli exclusion principle
- Real space distribution ions and electrons
- TFSF source  $E_y$
- CPML boundary condition in  $xy$  planes



# Process

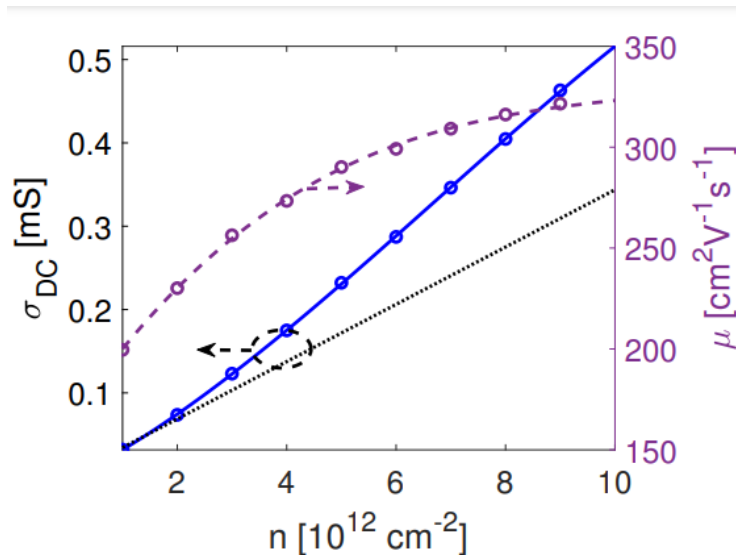


$$\sigma(\omega) = \frac{\langle \tilde{\mathbf{E}}(\omega) \rangle \cdot \langle \tilde{\mathbf{J}}(\omega) \rangle}{|\langle \tilde{\mathbf{E}}(\omega) \rangle|^2}$$



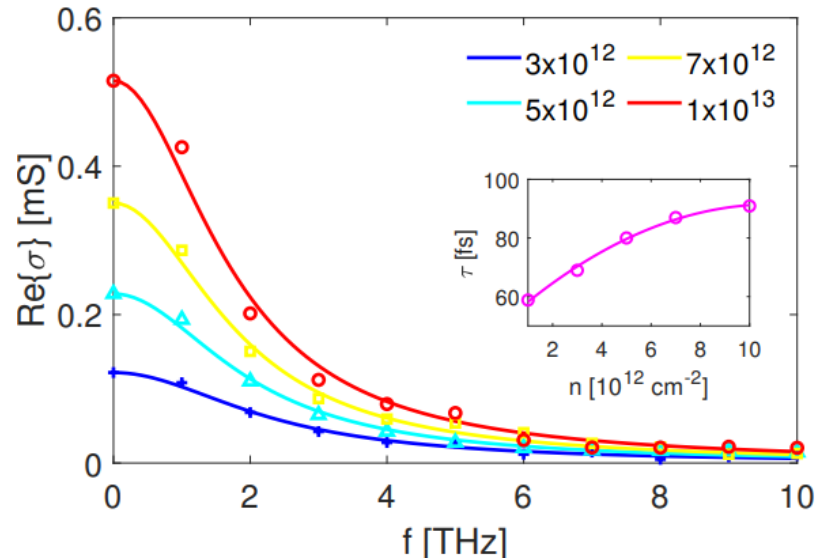
# Results

$\sigma_{dc}$  VS  $n$ :



- At low doping density, transport limited by ionized impurity scattering
- At high  $n$ , screening becomes important
- Mostly carrier independent  $\mu$  i.e., linear conductivity
- Almost full screening of impurities for carrier-to-impurity ratio of 10

# Results

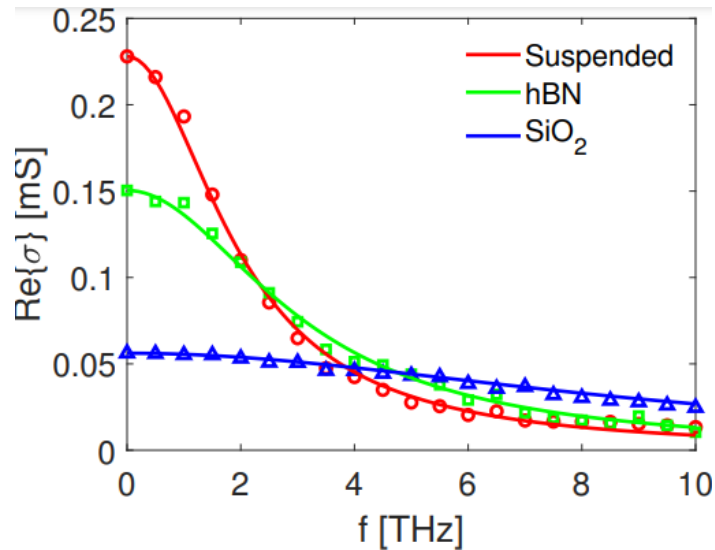


- 2D material with  $m^*$  → weak E dependent scattering → Drude model

$$\sigma(\omega) = \frac{\sigma_{dc}}{1 - i\omega\tau}$$

- $\sigma_{dc}$  limited by impurity at low  $n$ , phonon at high  $n$
- Effective relaxation time  $\tau$  approaches impurity free value of 90 fs

# Results



- Suspended MoS<sub>2</sub> → No dominant scattering mechanism
- Supported MoS<sub>2</sub> → SO phonon scattering dominates
- Weak polar HBN substrate → higher conductivity at low THz
- However, strong polar SiO<sub>2</sub> → retains  $\sigma$  at high THz

# Fitting parameters

Substrate	$n$ ( $\text{cm}^{-2}$ )	$\sigma_{\text{dc}}$ (mS)	$\tau$ (fs)
–	$3 \times 10^{12}$	0.1219	68.97
–	$5 \times 10^{12}$	0.2280	80.00
–	$7 \times 10^{12}$	0.3503	86.00
–	$10 \times 10^{12}$	0.5152	90.91
hBN	$5 \times 10^{12}$	0.1504	51.28
SiO <sub>2</sub>	$5 \times 10^{12}$	0.0562	16.67

For suspended MoS<sub>2</sub>,

$$\mu_{\text{dc}} = -1.683n^2 + 31.59n + 172.8, \text{ cm}^2\text{V}^{-1}\text{s}^{-1}$$

$$\tau = -0.34n^2 + 7.4n + 51.14, \text{ fs} \quad 10^{12} \leq n \leq 10^{13} \text{ cm}^{-2}$$

For HBN & SiO<sub>2</sub> supported MoS<sub>2</sub>,  $\tau$  and  $\mu$  are  $\sim 1.5$  and  $\sim 5$  times smaller.

# Conclusion

- EMC-FDTD numerical solver couples electrodynamics with carrier dynamics
- Tune impurity density, spatial impurity distribution, and carrier density
- Useful for extracting many body effects from experiments
- Useful for substrate selection for THz operation
- Can be readily extended to other TMDs and 2D materials

**Thanks!**